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S #	Comment	Database	Query String	Delete?
S436		TDBD	(crystal adj quality) and (intensity adj ratio)	☐
S435		DWPI	(crystal adj quality) and (intensity adj ratio)	☐
S434		JPAB	(crystal adj quality) and (intensity adj ratio)	☐
S433		EPAB	(crystal adj quality) and (intensity adj ratio)	☐
S432		PGPB	(crystal adj quality) and (intensity adj ratio)	☐
S431		USPT	(crystal adj quality) and (intensity adj ratio)	☐
S430		USPT	(polysilicon) and (intensity) and reflect$ and (first adj (detector or sensor)) and (second adj (detector or sensor)) and (beam adj splitter) and (splitting adj ratio)	☐
S429		PGPB	(polysilicon) and (intensity) and reflect$ and (first adj (detector or sensor)) and (second adj (detector or sensor)) and (beam adj splitter) and (splitting adj ratio)	☐
S428		USPT	(polysilicon) and (intensity) and reflect$ and (first adj (detector or sensor)) and (second adj (detector or sensor)) and (beam adj splitter) and (splitting adj ratio)	☐
S427		USPT	(polysilicon) and (intensity and ratio) and reflect$ and (first adj (detector or sensor)) and (second adj (detector or sensor)) and (beam adj splitter)	☐
			(polysilicon) and (intensity adj ratio) and reflect$ and (first adj (detector or sensor)) and	

S426		USPT	(second adj (detector or sensor)) and (beam adj splitter)	☐
S425		PGPB	(polysilicon) and (intensity adj ratio) and reflect$ and (first adj (detector or sensor)) and (second adj (detector or sensor)) and (beam adj splitter)	☐
S424		PGPB	(polysilicon) and (intensity) and reflect$ and (first adj (detector or sensor)) and (second adj (detector or sensor)) and (beam adj splitter)	☐
S423		USPT	(polysilicon) and (intensity) and reflect$ and (first adj (detector or sensor)) and (second adj (detector or sensor)) and (beam adj splitter)	☐
S422		USPT	(polysilicon) and (intensity) and reflect$ and (first adj (detector or sensor)) and (second adj (detector or sensor))	☐
S421		TDBD	inspect$ and (polysilicon adj (layer or surface or substrate)) and quality and reflect$ and (intensity adj ratio)	☐
S420		DWPI	inspect$ and (polysilicon adj (layer or surface or substrate)) and quality and reflect$ and (intensity adj ratio)	☐
S419		EPAB	inspect$ and (polysilicon adj (layer or surface or substrate)) and quality and reflect$ and (intensity adj ratio)	☐
S418		JPAB	inspect$ and (polysilicon adj (layer or surface or substrate)) and quality and reflect$ and (intensity adj ratio)	☐
S417		PGPB	inspect$ and (polysilicon adj (layer or surface or substrate)) and quality and reflect$ and (intensity adj ratio)	☐
S416		PGPB	inspect$ and (polysilicon adj (layer or surface or substrate)) and quality and reflect$ and intensity and ratio	☐
S415		USPT	inspect$ and (polysilicon adj (layer or surface or substrate)) and quality and reflect$ and intensity and ratio	☐
S414		USPT	inspect$ and (polysilicon adj (layer or surface or substrate)) and quality and reflect$ and intensity	☐
S413		USPT	inspect$ and (polysilicon adj (layer or surface or substrate)) and quality and reflect$	☐

S412		USPT	inspect$ and (polysilicon adj (layer or surface or substrate)) and quality	☐
S411		USPT	inspect$ and (polysilicon adj (layer or surface or substrate))	☐
S410		USPT	inspect$ and (polysilicon ajd (layer or surface or substrate))	☐
S409		USPT	inspect$ and quality and (polysilicon ajd (layer or surface or substrate))	☐
S408		TDBD	(polysilicon) and substrate and (beam adj splitter) and (intensity adj ratio) and reflect$	☐
S407		DWPI	(polysilicon) and substrate and (beam adj splitter) and (intensity adj ratio) and reflect$	☐
S406		JPAB	(polysilicon) and substrate and (beam adj splitter) and (intensity adj ratio) and reflect$	☐
S405		EPAB	(polysilicon) and substrate and (beam adj splitter) and (intensity adj ratio) and reflect$	☐
S404		PGPB	(polysilicon) and substrate and (beam adj splitter) and (intensity adj ratio) and reflect$	☐
S403		USPT	(polysilicon) and substrate and (beam adj splitter) and (intensity adj ratio) and reflect$	☐
S402		USPT	250/$.ccls. and (polysilicon) and substrate and (beam adj splitter) and (intensity adj ratio) and reflect$	☐
S401		USPT	250/$.ccls. and (polysilicon) and substrate and (first adj light) and (second adj light) and (beam adj splitter) and (intensity adj ratio)	☐
S400		USPT	(direct adj conver$) and (indirect adj conver$) and image and charge	☐
S399		USPT	(direct adj conver$) and (indirect adj conver$) and image and charge	☐
S398		USPT	(direct adj conver$) and (indirect adj conver$)	☐
S397		USPT	(direct adj convert$) and (indirect adj convert$)	☐
S396		USPT	6185274.pn. and (convert$)	☐
S395		USPT	6185275.pn. and (convert$)	☐
S394		USPT	6674470.pn. and (convert$)	☐
S393		USPT	6674470.pn. and (conversion) and scintillat$	